

METHOD FOR MANUFACTURING A SEMICONDUCTOR DEVICE

ABSTRACT OF THE DISCLOSURE

5 A method of forming patterns in a semiconductor device comprises:
forming a conductive film on a substrate; forming an anti-reflective layer on the
conductive film; cleaning oxide residues on the anti-reflective layer using a first
cleaning solution; cleaning the oxide residues on the anti-reflective layer using a
second cleaning solution; forming a photoresist pattern on the anti-reflective
layer; and patterning the conductive film using the photoresist pattern.